

## UMF Equipment – Harrick Plasma Cleaner

Plasma cleaner is the removal of impurities and contaminants from surfaces through the use of an energetic plasma created from gaseous species, such as oxygen. The plasma is created by using high frequency voltages (typically kHz to >MHz) to ionise the low pressure gas. It serves as excellent tool for surface cleaning, surface preparation and surface modification. Plasma treatment may be applied to a wide variety of materials, including metals, ceramics, composites, plastics, polymers and biomaterials.

- Features:
- Chamber size: 6" Dia. x 6.5" L
  - RF Power: 45W Maximum
  - RF power settings: Adjustable (Low: 30W, Medium: 38W, High: 45W)
  - Process gas: O<sub>2</sub>, N<sub>2</sub>

Please refer to supplier information page: <https://harrickplasma.com/> for further details of the system.  
For any inquiry, please contact Dr. Terence Wong (Tel: 3400 2075; Email: [tai-lun.wong@polyu.edu.hk](mailto:tai-lun.wong@polyu.edu.hk)).



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